

X = 2.1 mm Y = 1.55 mm

### **Product Features**

RF frequency: 13.5 to 15.5 GHz

■ Linear Gain: 13 dB typ.

■ Psat: 42 dBm typ.

■ PAE% @ Psat: 43% typ.

■ Die Size: 3.255 sq. mm.

0.2um GaN HEMT Process

4 mil SiC substrate

■ DC Power: 28 VDC @ 640 mA

### **Applications**

- Point-to-Point Digital Radios
- Point-to-Multipoint Digital Radios
- SATCOM Terminals

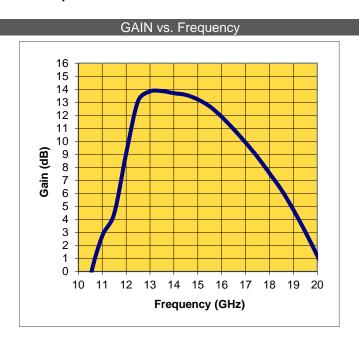
### **Product Description**

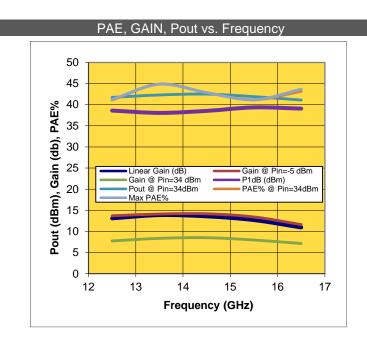
The APN232 monolithic GaN HEMT amplifier is a broadband, single-stage power device, designed for use in SATCOM Terminals and point-to-point digital radios. To ensure rugged and reliable operation, HEMT devices are fully passivated. Both bond pad and backside metallization are Au-based that is compatible with epoxy and eutectic die attach methods.

### Performance Characteristics (Ta = 25°C)

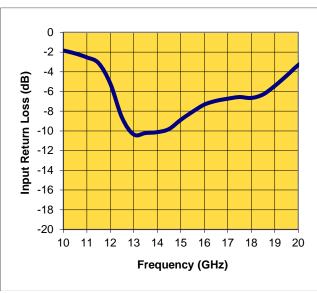
Specification	Min	Тур	Max	Unit
Frequency	13.5		14	GHz
Linear Gain	12	13		dB
Input Return Loss	7	10		dB
Output Return Loss	5	9		dB
P1dB (PP*)		38.5		dBm
Psat (PP*)	38.5	42		dBm
PAE @ Psat (PP*)		43		%
Vd		28		V
Vg		-3.5		V
Id		640		mA

### On wafer measured Performance Characteristics (Typical Performance at 25°C) Vd = 28 V, Id = 640 mA. \*

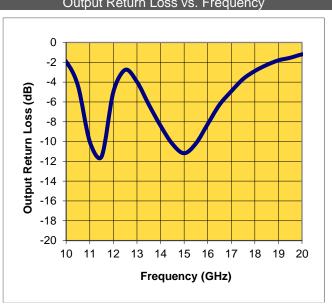






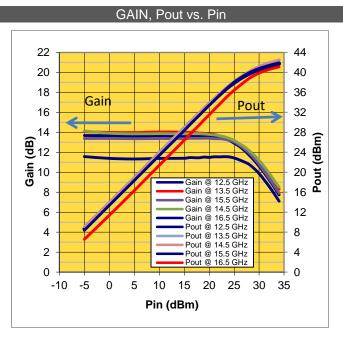


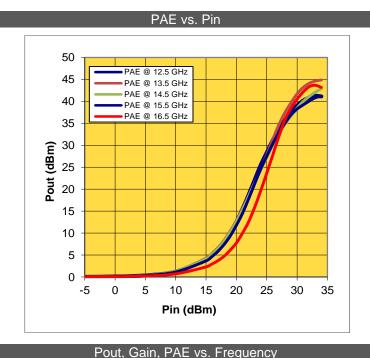
#### Output Return Loss vs. Frequency

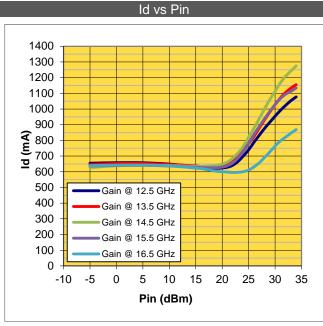


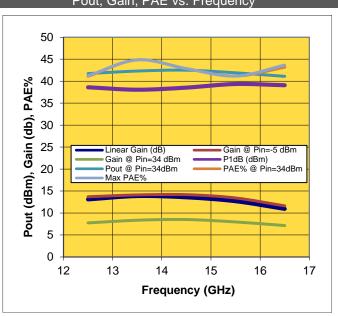
<sup>\*</sup>Pulsed-power on-wafer

## On wafer measured Performance Characteristics (Typical Performance at 25°C) Vd = 28 V, Id = 640 mA. \*



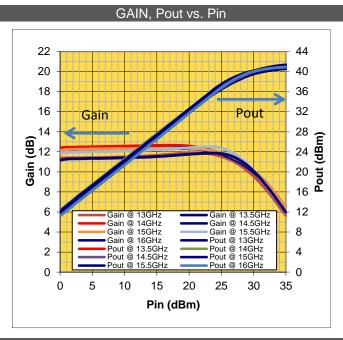


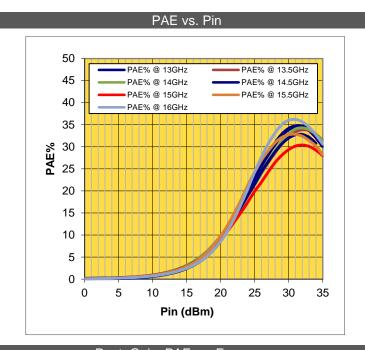


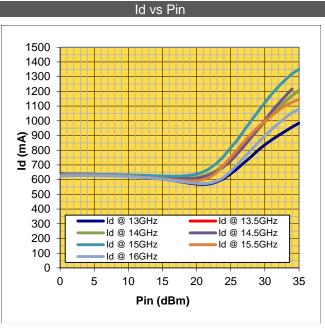


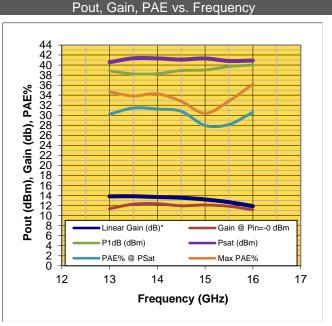
<sup>\*</sup>Pulsed-power on-wafer

# Measured fixture Performance Characteristics (Typical Performance at 25°C) Vd = 28 V, Id = 640 mA. \*\*



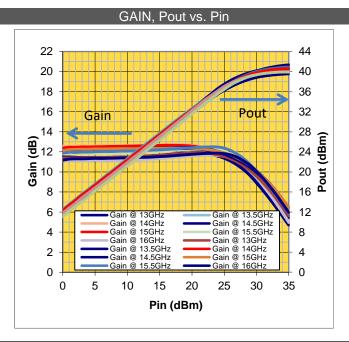


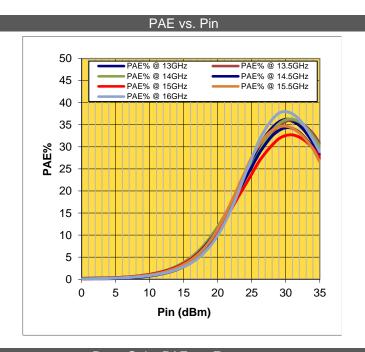


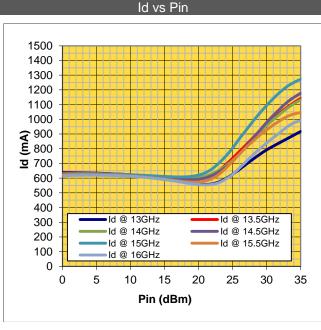


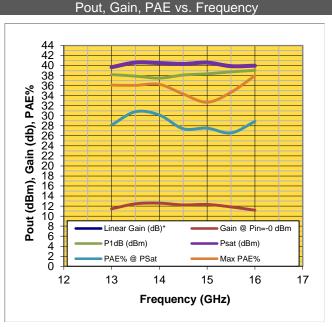
<sup>\*\*</sup>CW Fixture \*On-wafer Pulsed Power

# Measured fixture Performance Characteristics (Typical Performance at 25°C) Vd = 24 V, Id = 640 mA. \*\*



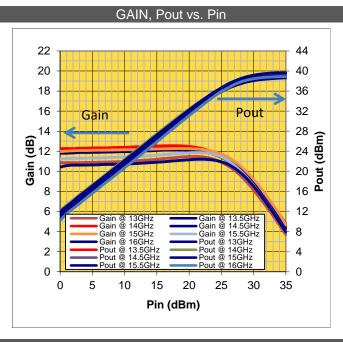


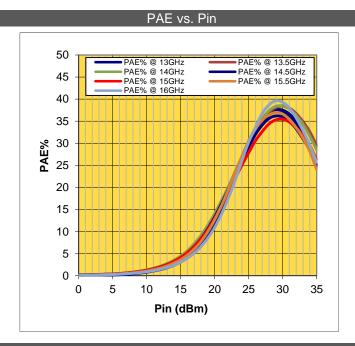


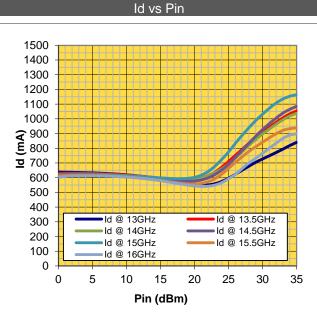


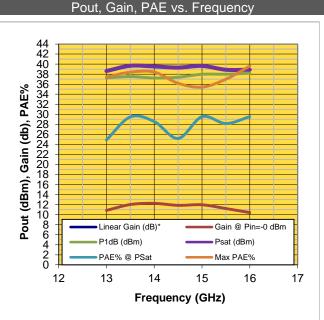
\*\*CW Fixture \*On-wafer Pulsed Power

# Measured fixture Performance Characteristics (Typical Performance at 25°C) Vd = 20 V, Id = 640 mA. \*\*







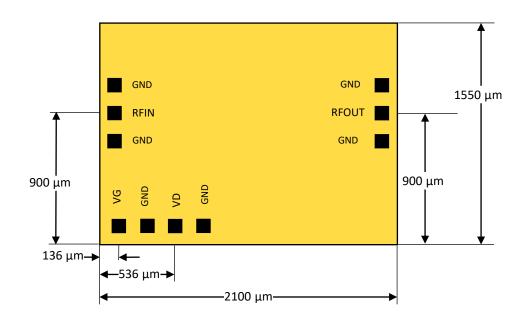


<sup>\*\*</sup>CW Fixture \*On-wafer Pulsed Power

# NORTHROP GRUMMAN

### **Die Size and Bond Pad Locations (Not** to Scale)

 $X = 2100 \pm 25 \ \mu m$   $Y = 1550 \pm 25 \ \mu m$ DC Bond Pad =  $100 \times 100 \pm 0.5 \ \mu m$ RF Bond Pad =  $100 \times 100 \pm 0.5 \ \mu m$ Chip Thickness =  $101 \pm 5 \ \mu m$ 



### **Biasing/De-Biasing Details:**

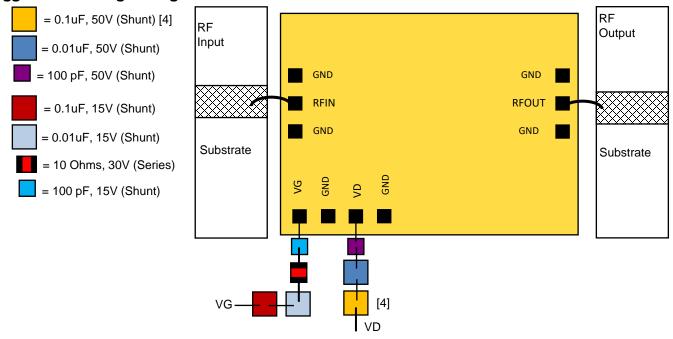
APN232 can only be biased at the bottom of the die.

Listed below are some guidelines for GaN device testing and wire bonding:

- a. Limit positive gate bias (G-S or G-D) to < 1V
- b. Know your devices' breakdown voltages
- c. Use a power supply with both voltage and current limit.
- d. With the power supply off and the voltage and current levels at minimum, attach the ground lead to your test fixture.
  - i. Apply negative gate voltage (-5 V) to ensure that all devices are off
  - ii. Ramp up drain bias to ∼10 V
  - iii. Gradually increase gate bias voltage while monitoring drain current until 20% of the operating current is achieved
  - iv. Ramp up drain to operating bias
  - v. Gradually increase gate bias voltage while monitoring drain current until the operating current is achieved
- e. To safely de-bias GaN devices, start by debiasing output amplifier stages first (if applicable):
  - . Gradually decrease drain bias to 0 V.
  - ii. Gradually decrease gate bias to 0 V.
  - iii. Turn off supply voltages

# NORTHROP GRUMMAN

#### Suggested Bonding Arrangement



#### **Recommended Assembly Notes**

- 1. Bypass caps should be 100 pF (approximately) ceramic (single-layer) placed no farther than 30 mils from the amplifier.
- 2. Best performance obtained from use of <10 mil (long) by 3 by 0.5 mil ribbons on input and output.
- 3. Part must be biased from both sides as indicated.
- 4. The 0.1uF, 50V capacitors are not needed if the drain supply line is clean. If Drain Pulsing of the device is to be used, do **NOT** use the 0.1uF, 50V Capacitors.

#### **Mounting Processes**

Most Northrop Grumman Aerospace Systems (NGAS) GaN IC chips have a gold backing and can be mounted successfully using either a conductive epoxy or AuSn attachment. NGAS recommends the use of AuSn for high power devices to provide a good thermal path and a good RF path to ground. Maximum recommended temp during die attach is 320°C for 30 seconds.

**Note**: Many of the NGAS parts do incorporate airbridges, so caution should be used when determining the pick up tool.

**CAUTION**: THE IMPROPER USE OF AuSn ATTACHMENT CAN CATASTROPHICALLY DAMAGE GaN CHIPS.

## PLEASE ALSO REFER TO OUR "Gan Chip Handling Application Note" BEFORE HANDLING, ASSEMBLING OR BIASING THESE MMICS!